

FIG. 1A

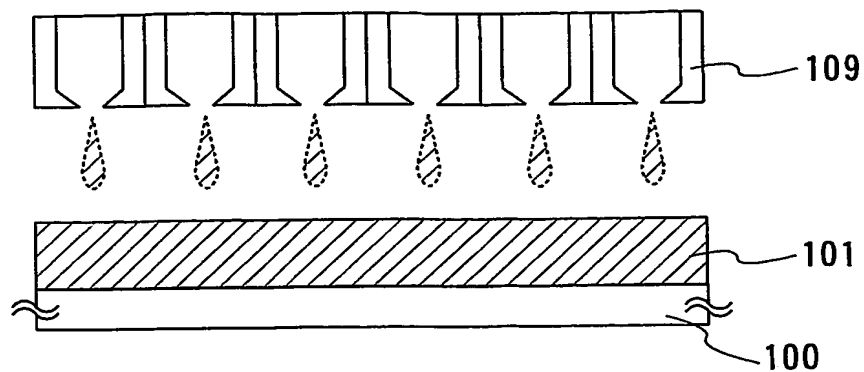


FIG. 1B

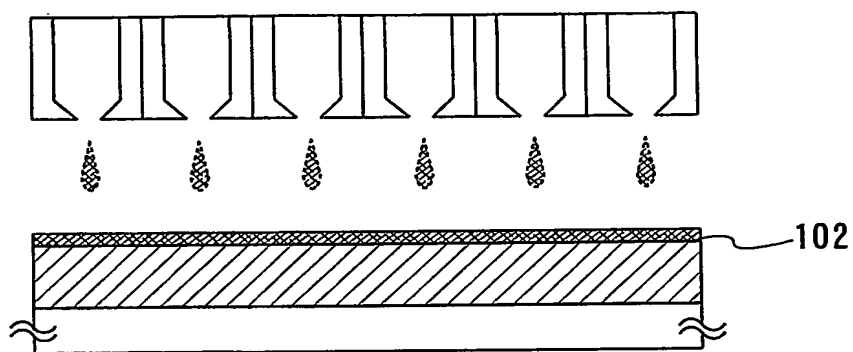


FIG. 1C

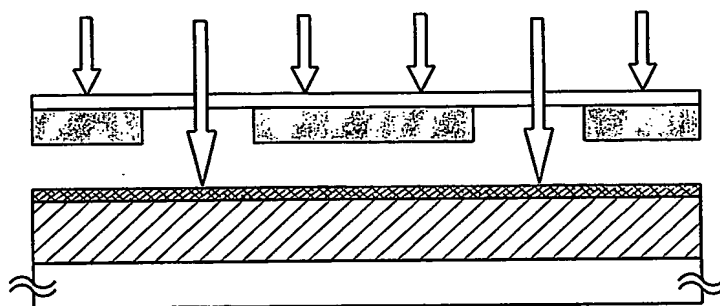


FIG. 1D

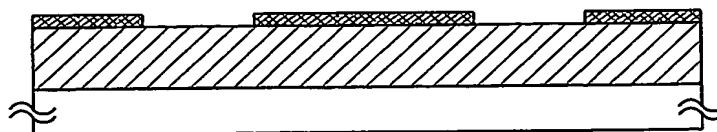
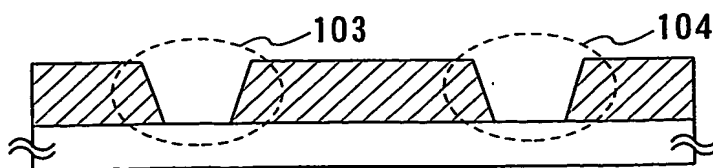


FIG. 1E



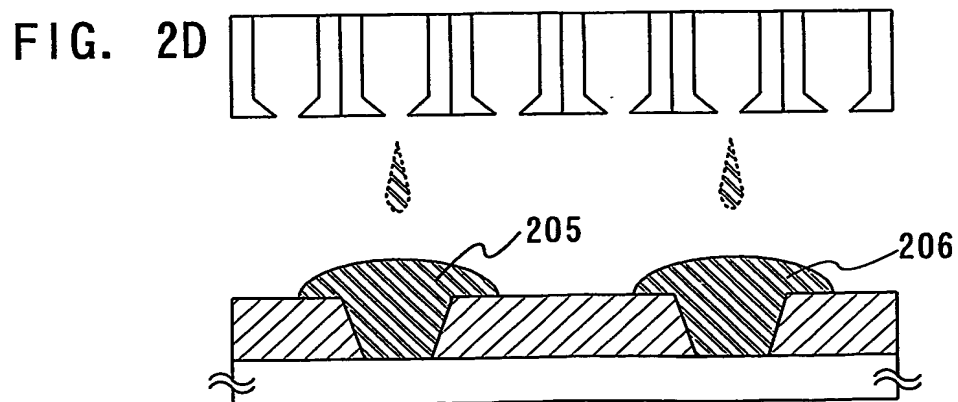
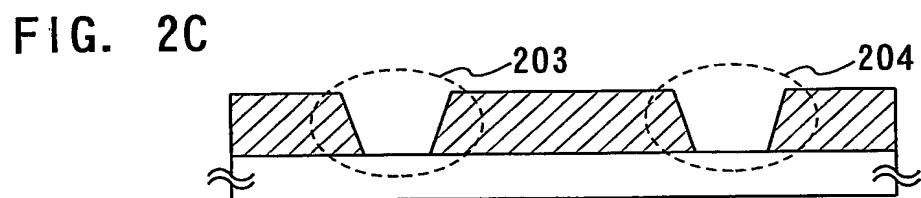
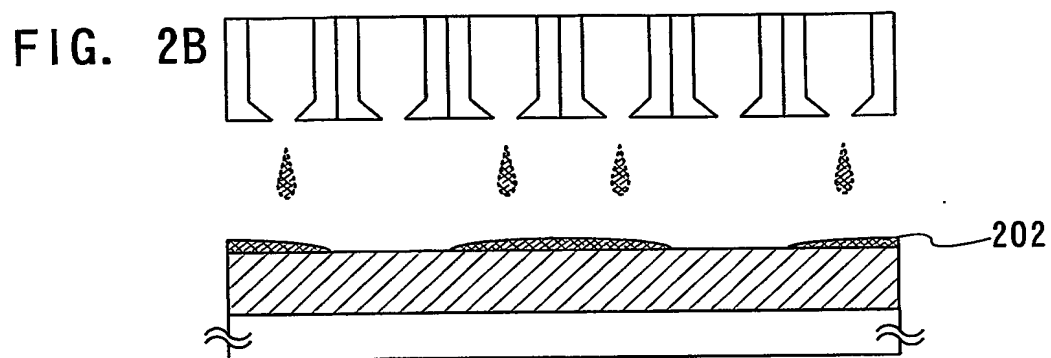
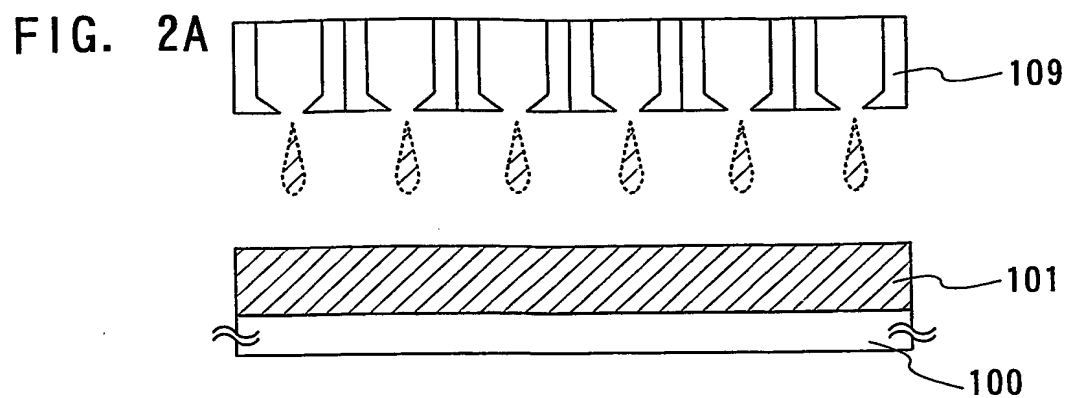


FIG. 3A

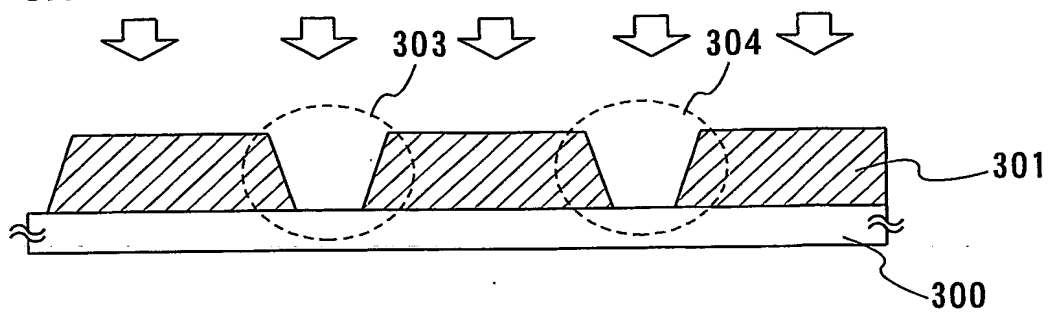
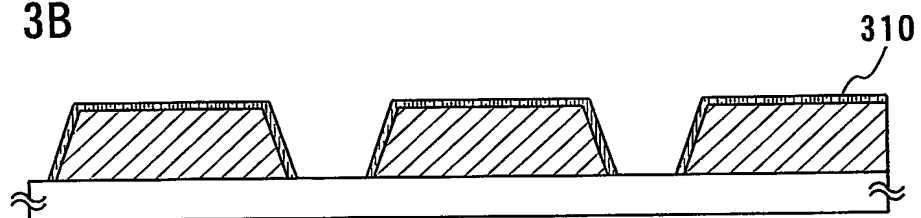


FIG. 3B



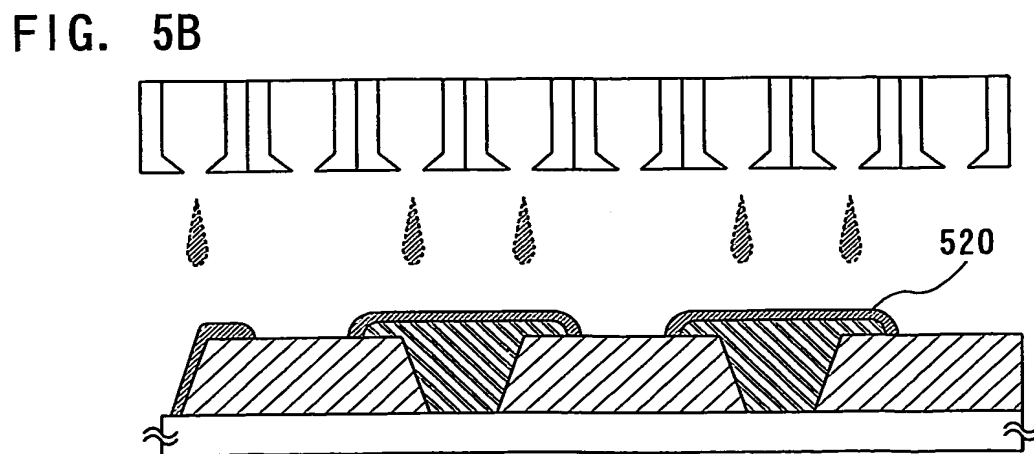
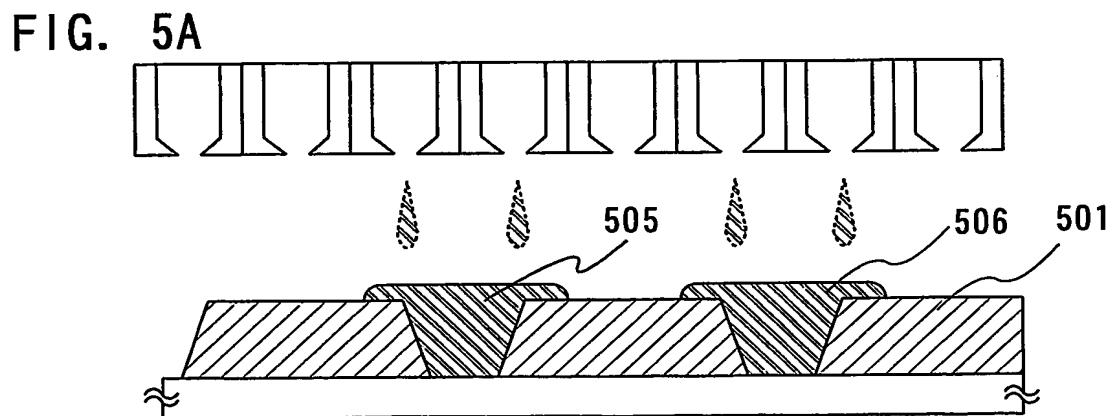
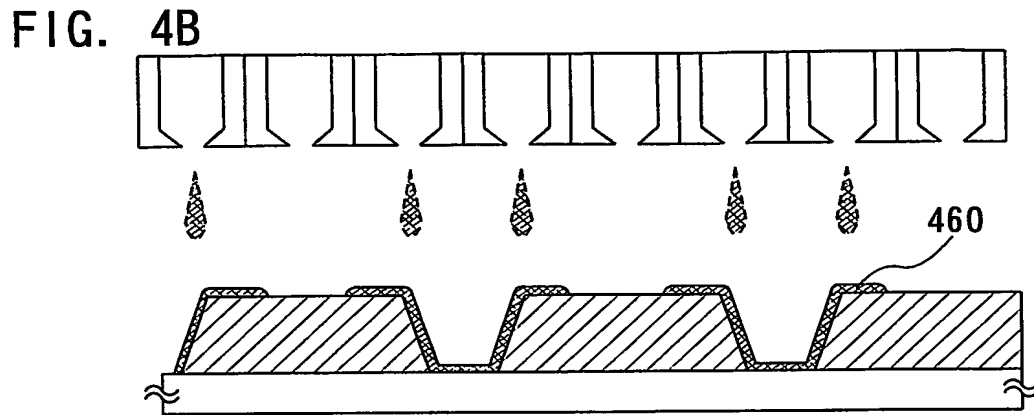
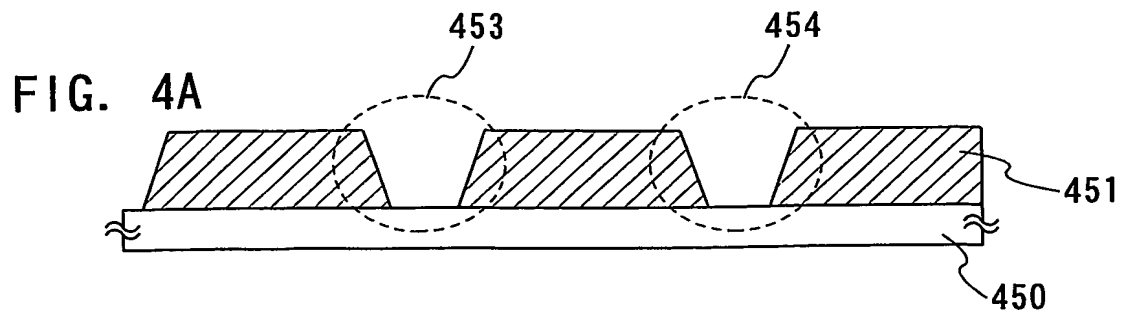


FIG. 6A

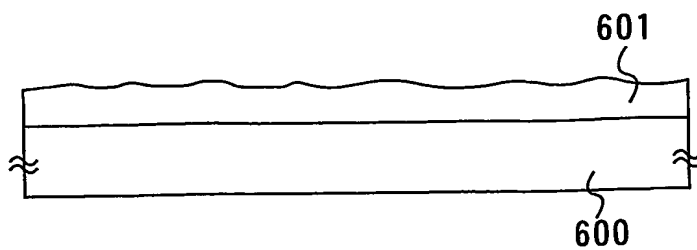


FIG. 6B

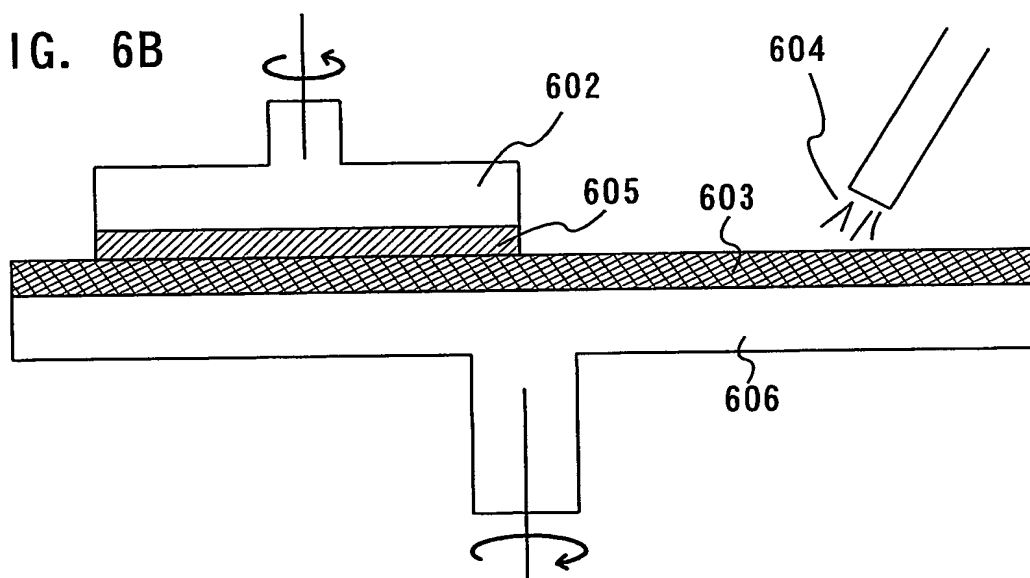


FIG. 6C

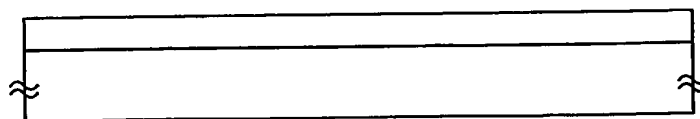


FIG. 7A

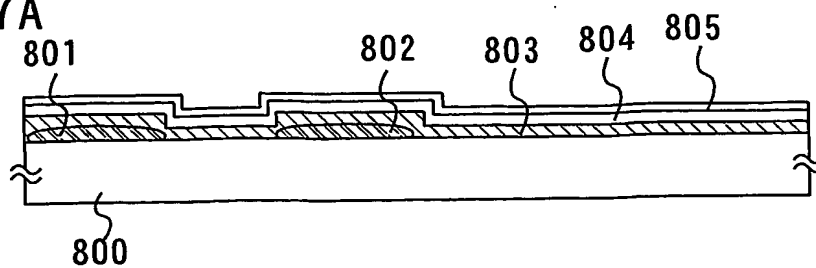


FIG. 7B

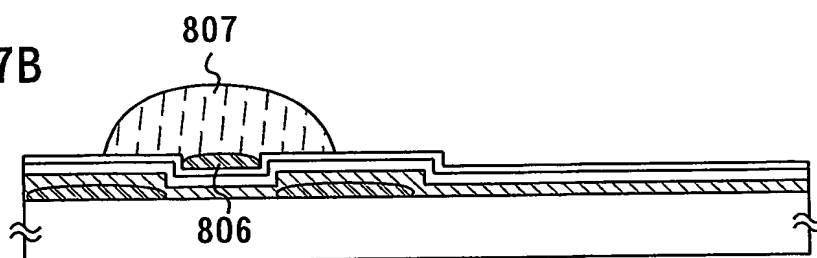


FIG. 7C

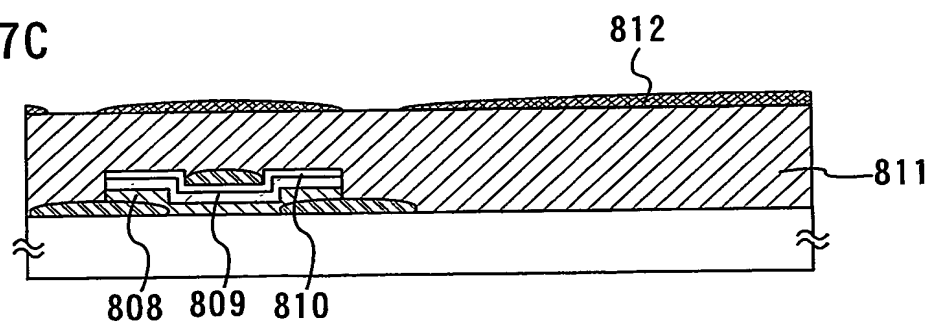
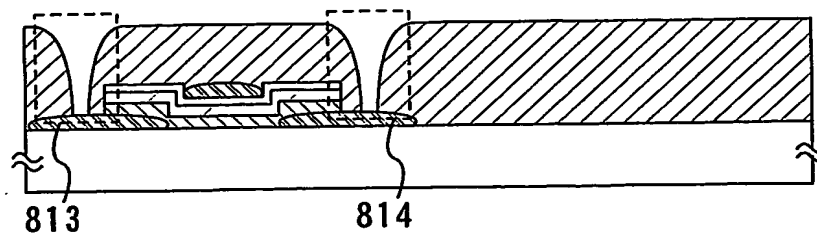


FIG. 7D



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FIG. 8A

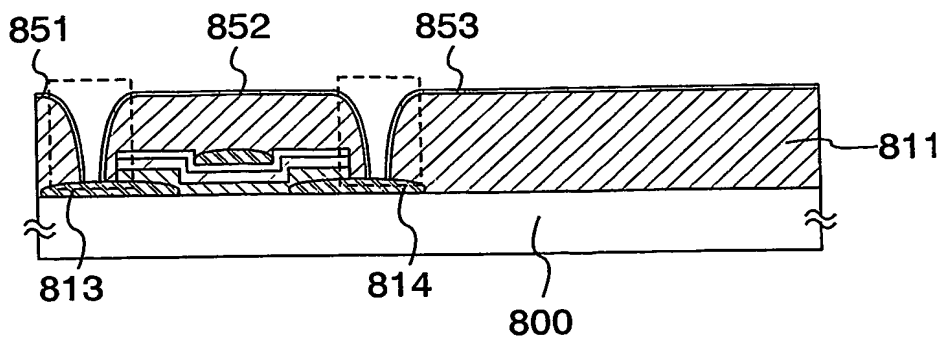


FIG. 8B

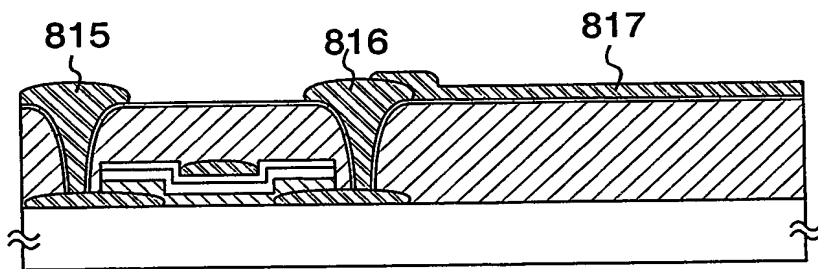
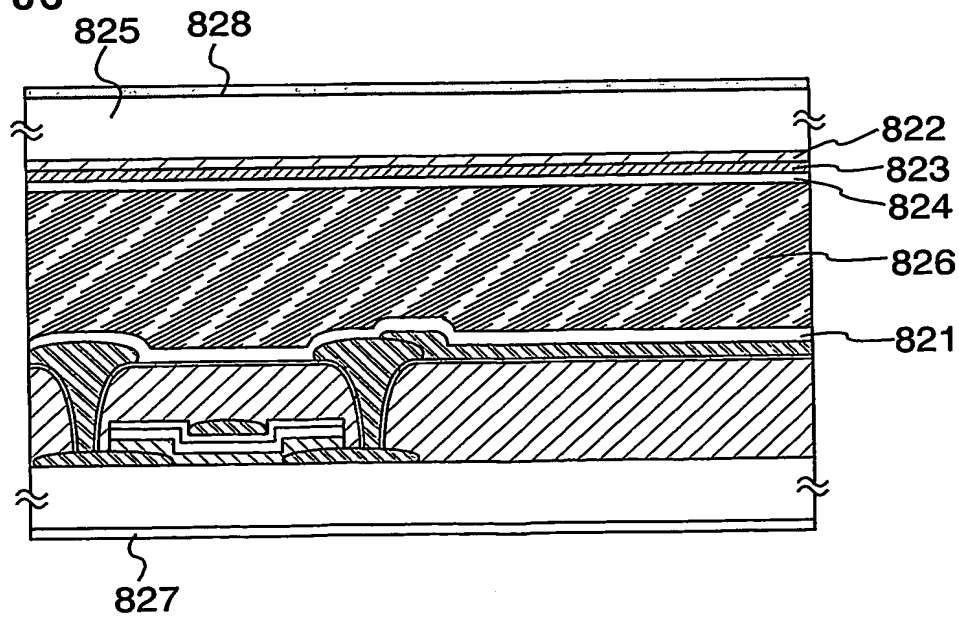


FIG. 8C



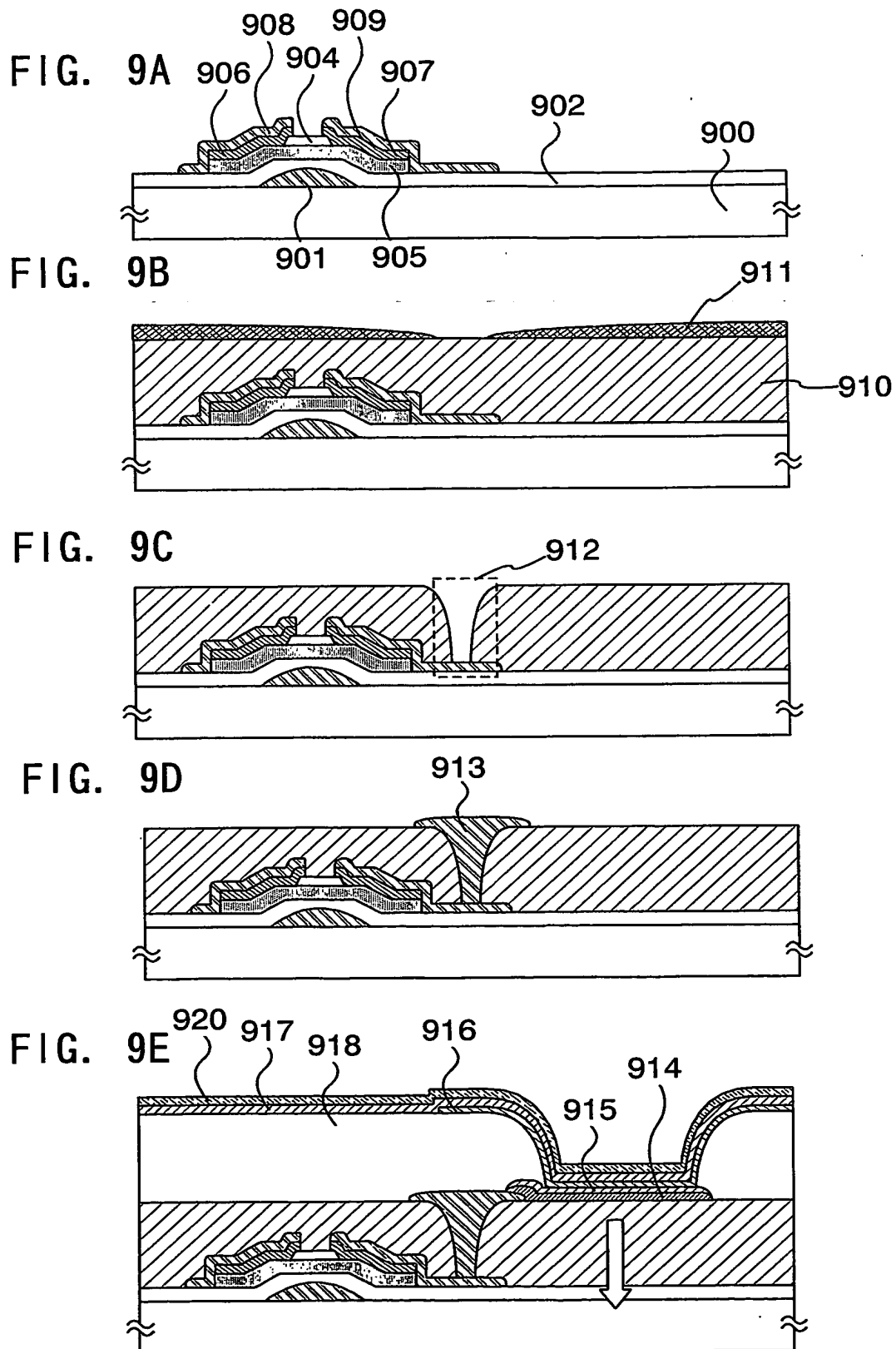




FIG. 10A

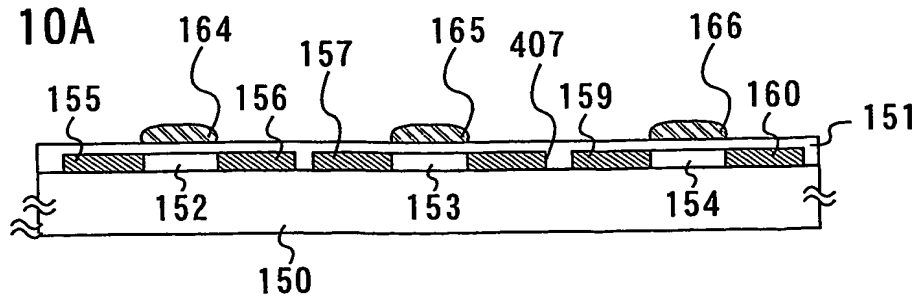


FIG. 10B

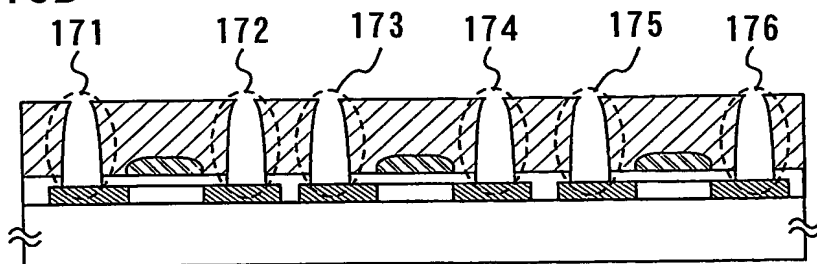


FIG. 10C

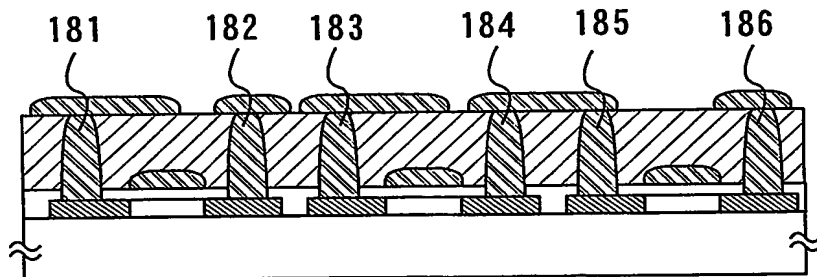


FIG. 10D

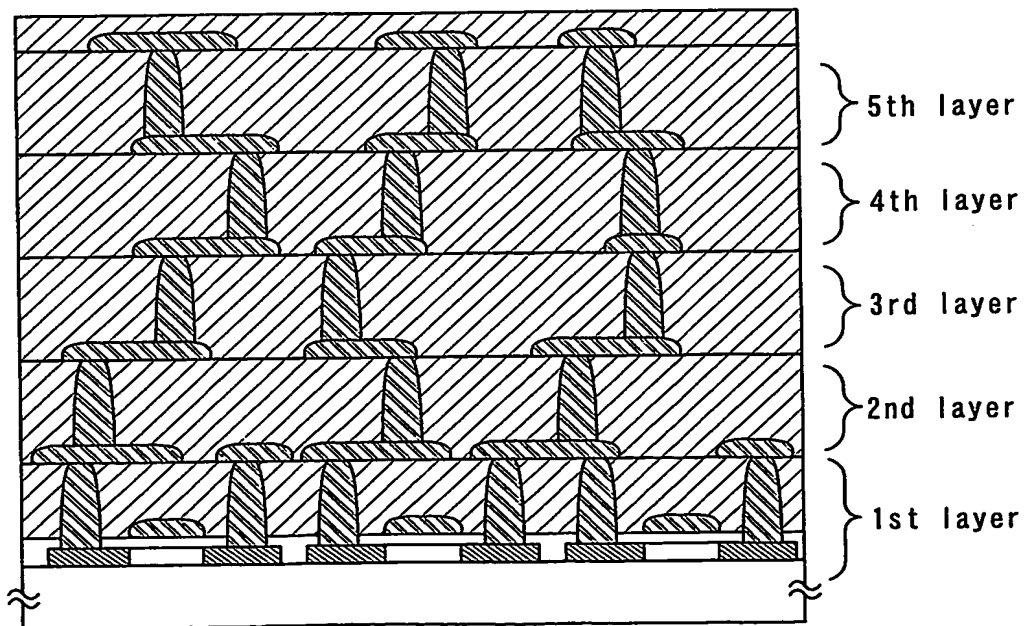


FIG. 11A

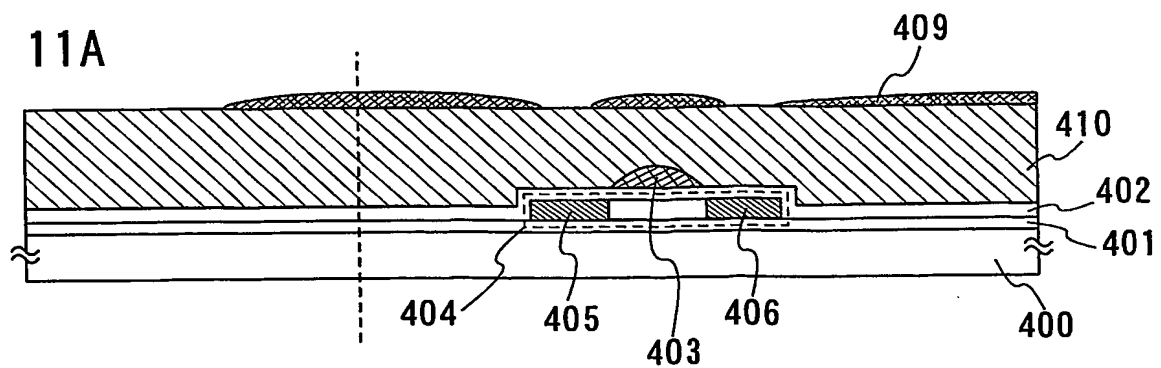


FIG. 11B

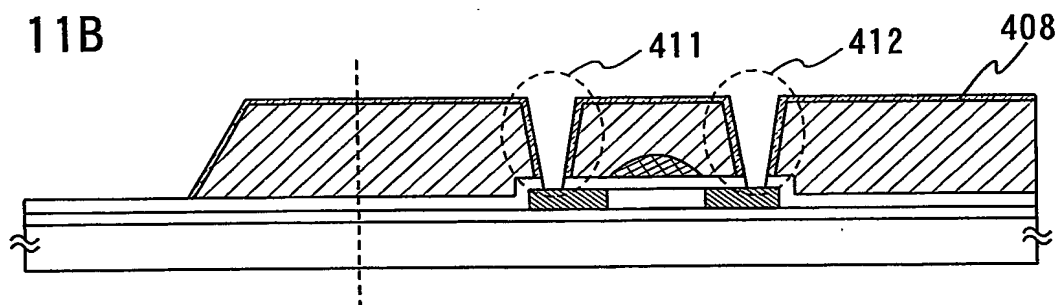


FIG. 11C

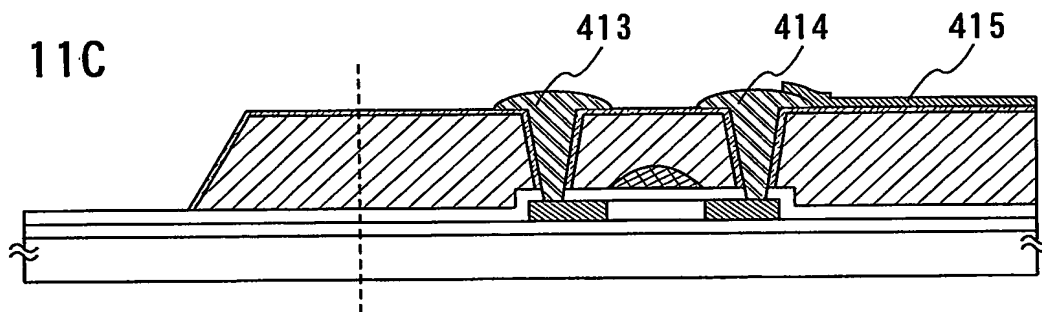
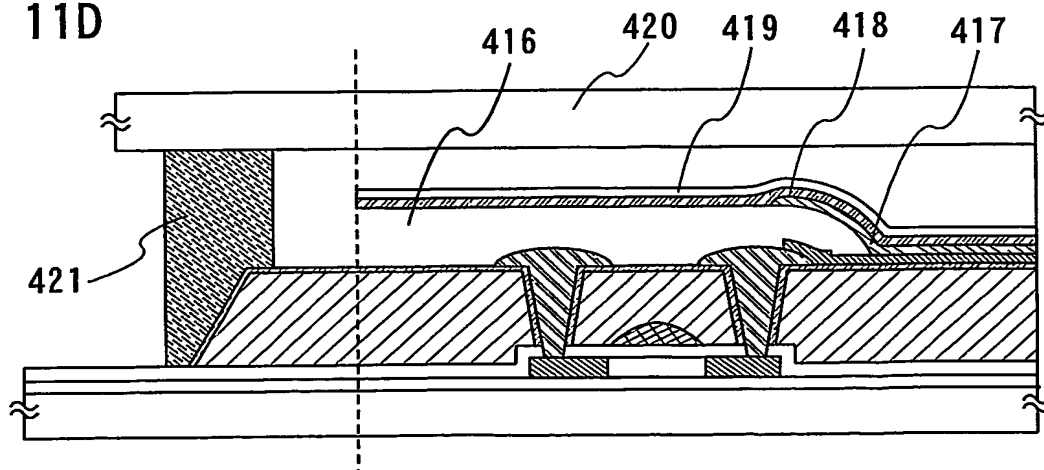


FIG. 11D



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FIG. 12A

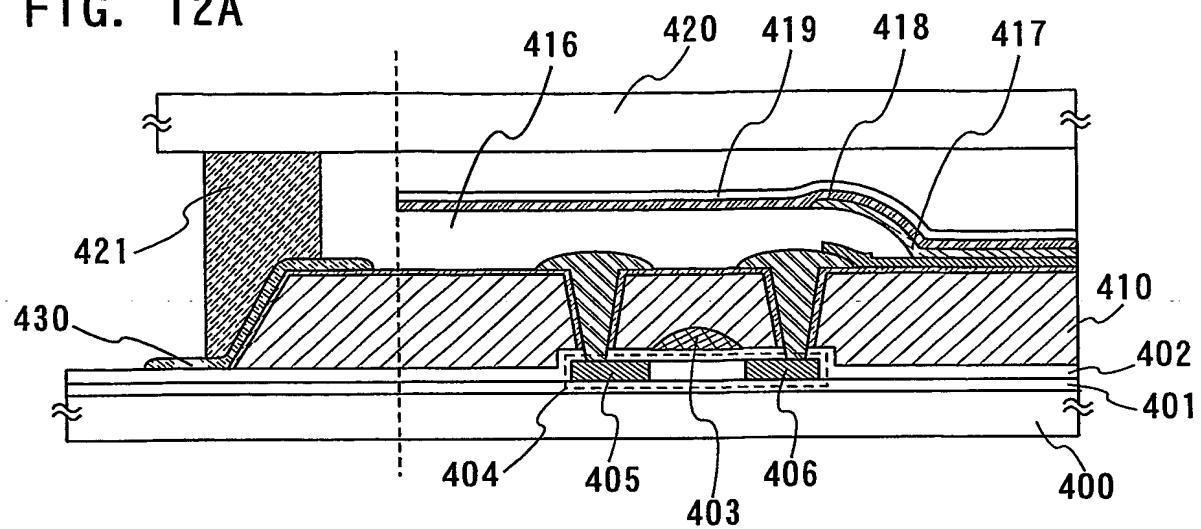


FIG. 12B

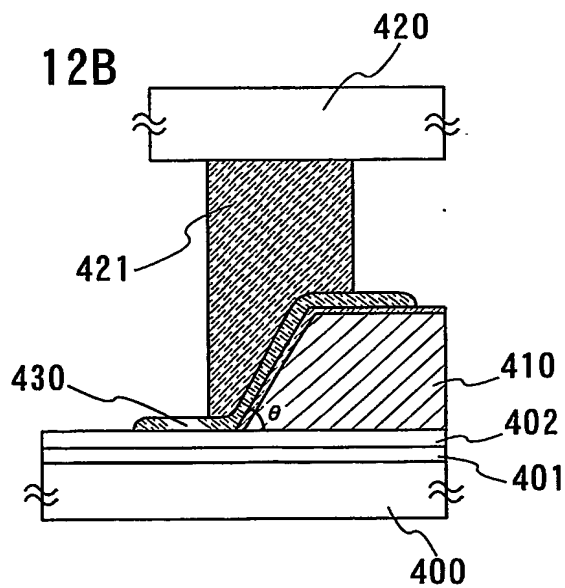


FIG. 13

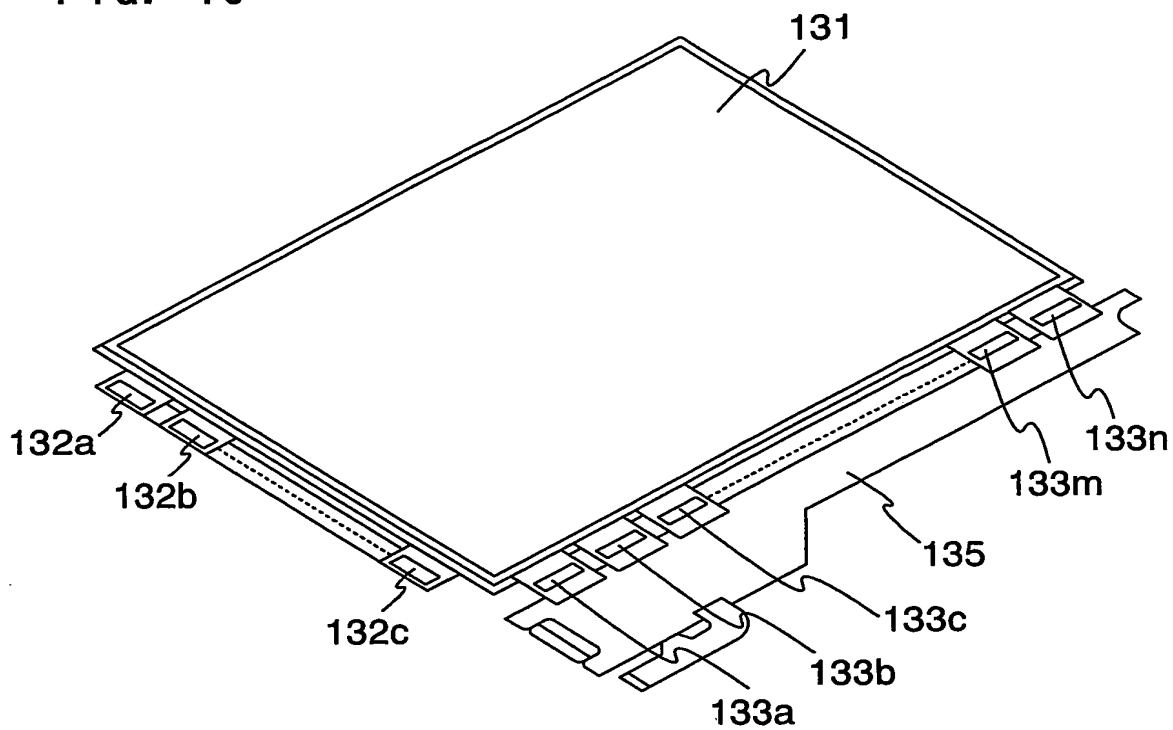


FIG. 14A

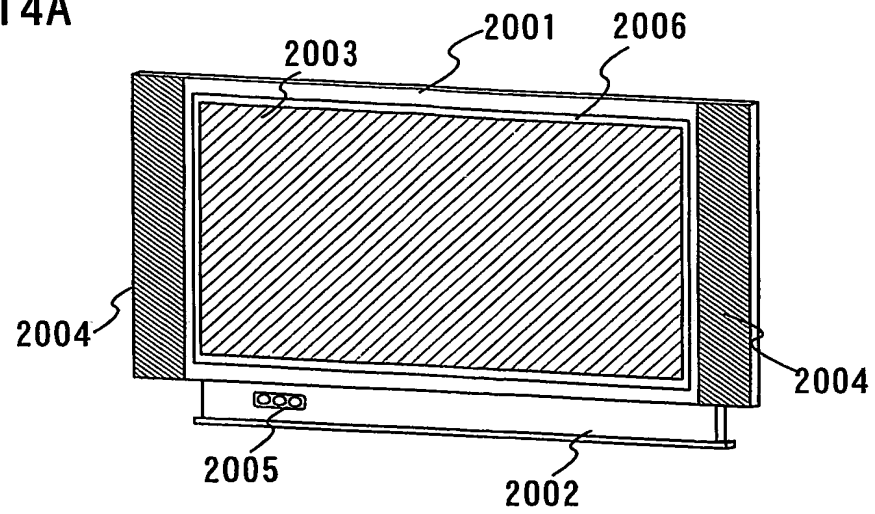


FIG. 14B

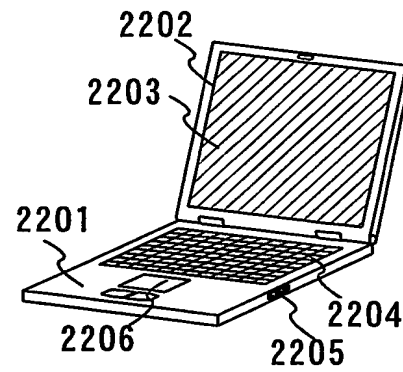
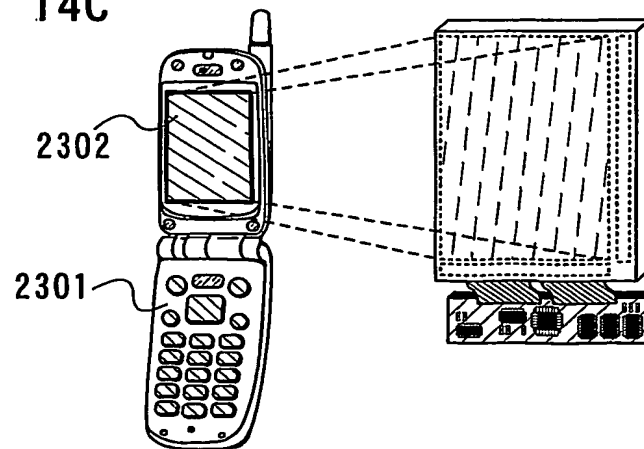


FIG. 14C



EXPLANATION OF REFERENCE

100·Substrate, 101·First insulating film, 102·Second insulating film, 103, 104·Openings, 202·Second insulating film, 203, 204·Openings, 205, 206·Conductive films, 300·Substrate, 301·Insulating film, 303, 304·Openings, 400·Substrate, 401·Base insulating film, 402·Insulating film, 403·Gate electrode, 404·Semiconductor film, 405·Source, 406·Drain, 409, 410·Insulating films, 411, 412·Openings, 413, 414·Conductive films, 415·Pixel electrode, 416·Bank, 417·Electroluminescent layer, 418·Conductive film, 419·Insulating film, 420·Substrate, 421·Sealant, 450·Substrate, 451·Insulating film, 453, 454·Openings, 460·Barrier layer, 501·Insulating film, 505, 506·Conductive films, 520·Barrier layer, 600·Substrate, 601·Insulating film, 602·Head, 603·Abrasive cloth, 604·Abrasive liquid, 605·Wafer, 606·Molding board, 800, 825·Substrates, 801, 802·Conductive films, 803·n-type amorphous semiconductor, 804·Amorphous semiconductor, 805·Insulating film, 806·Gate electrode, 807·Mask, 808·n-type amorphous semiconductor, 809·Amorphous semiconductor, 810·Insulating film, 811, 812·Insulating films, 813, 814·Openings, 815, 816·Conductive films, 817·Pixel electrode, 821, 824·Oriented films, 822·Color filter, 823·Counter electrode, 824·Substrate, 826·Liquid crystal, 827, 828·Polarizing plates, 900·Substrate, 901·Gate electrode, 902·Insulating film, 905·Amorphous semiconductor, 906, 907·n-type amorphous semiconductor, 908, 909·Conductive films, 910, 911·Insulating films, 912·Openings, 913, 914·Conductive films, 915·Anode, 916·Electroluminescent layer, 917, Cathode, 918·Bank, 920·Shielding material